

# 大面積Micro Pixel Chamberの開発 3

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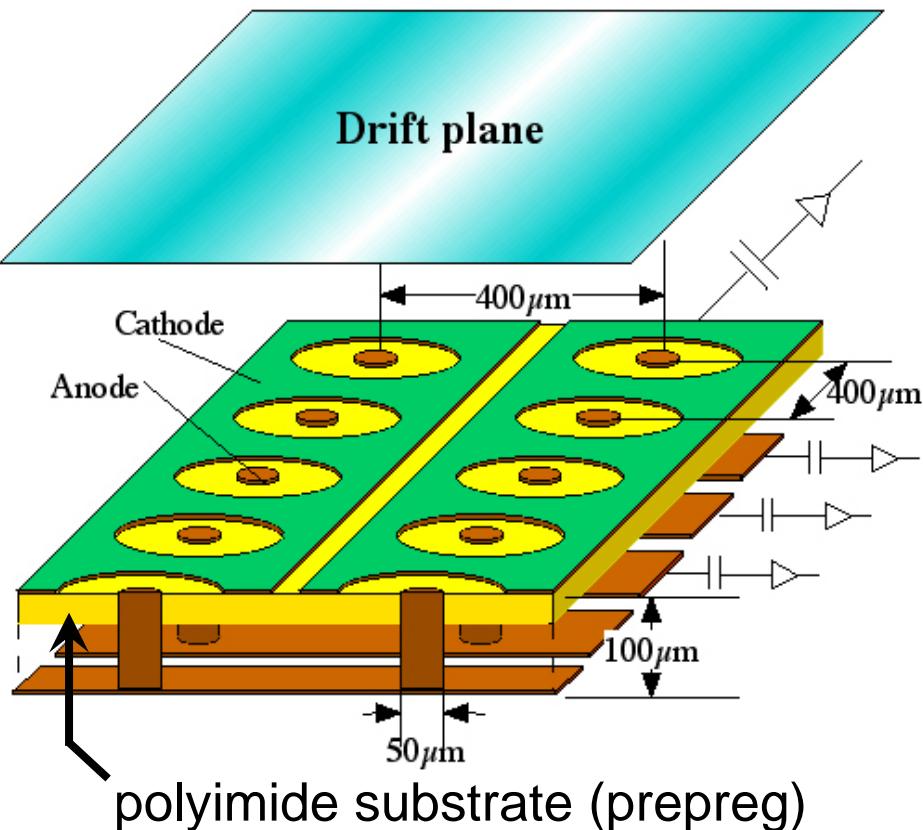
# 日本物理学会2003年秋季大会 @宮崎ワールドコンベンションセンター・サミット



# *Contents*

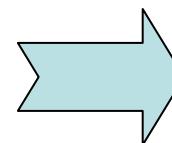
1. Micro Pixel Chamber ( $\mu$ -PIC)
2. Optimization of electrode structure
  - Simulation of electron drift
  - New manufacture technique
3. Basis for MeV gamma-ray imaging
  - $\text{CF}_4$  gas
  - Gas vessel
4. Summary

# 1.1 Micro Pixel Chamber ( $\mu$ -PIC)

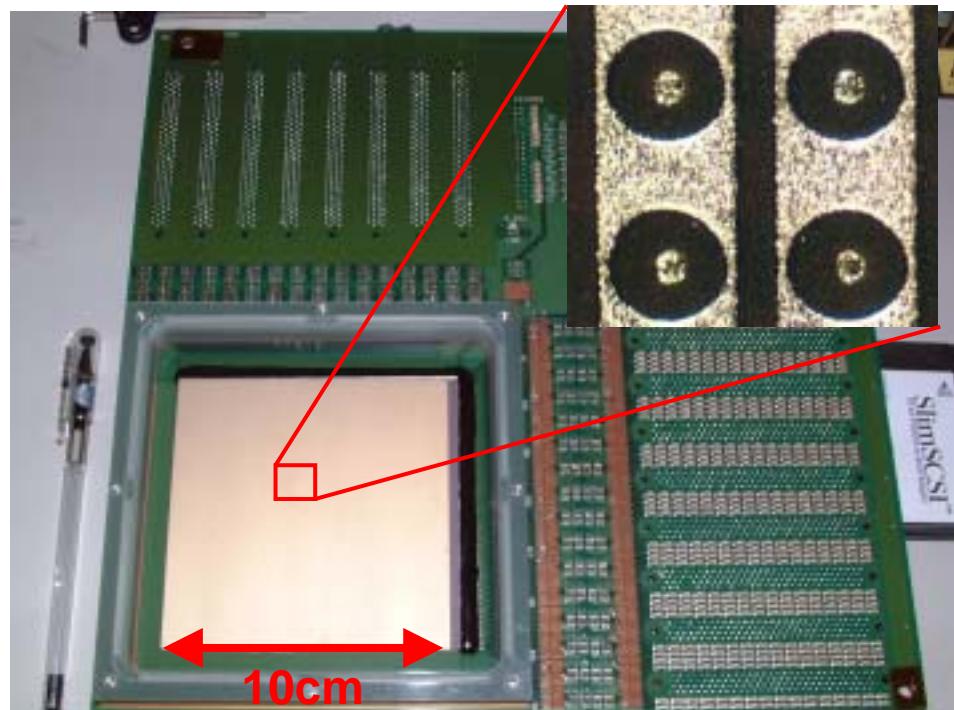


- $400\mu\text{m}$  pitch electrodes
- 256 anodes and  
256 cathodes

Printed Circuit Board (PCB)  
technology



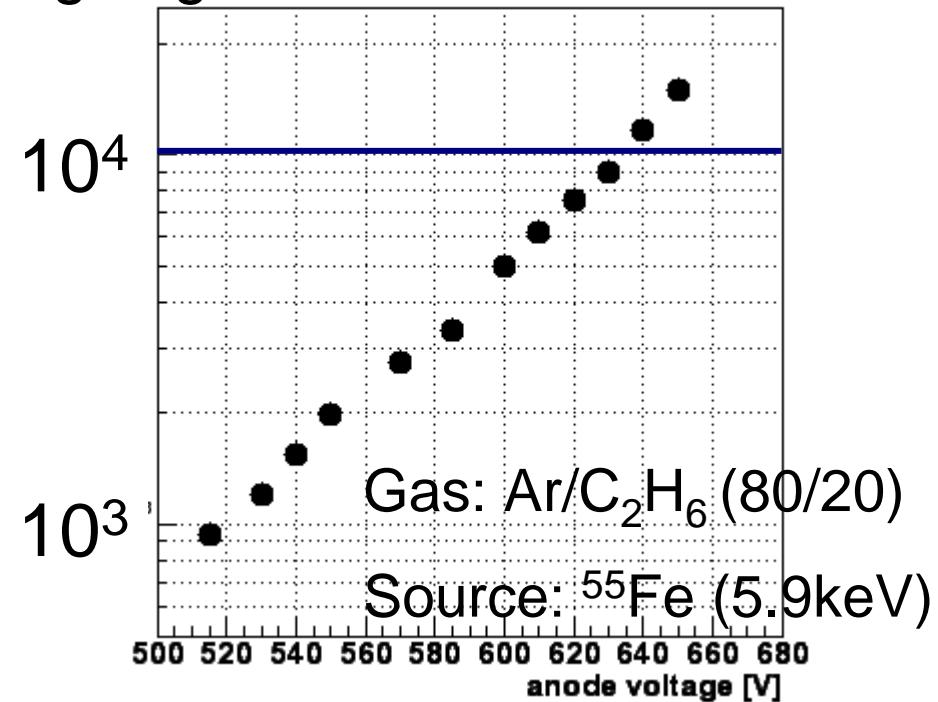
- Large area
- Low cost



Detection area =  $100\text{cm}^2$

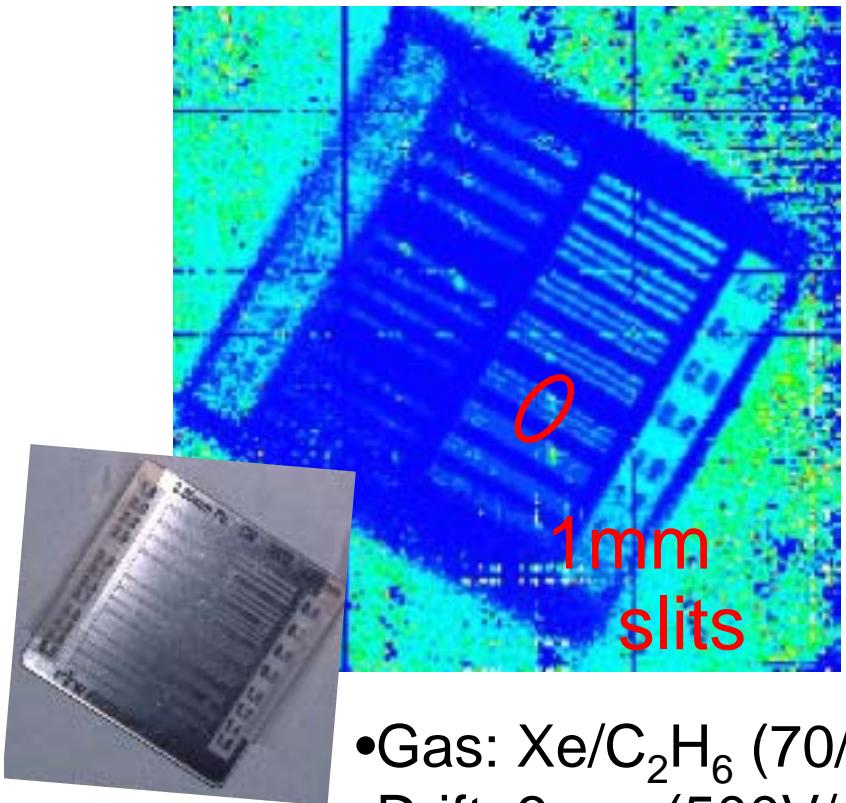
# 1.2 Performances

gas gain



- Gas gain ~ 15,000 (max)
- Stable operation (>1000h) @ gas gain ~ 5000

X-ray imaging

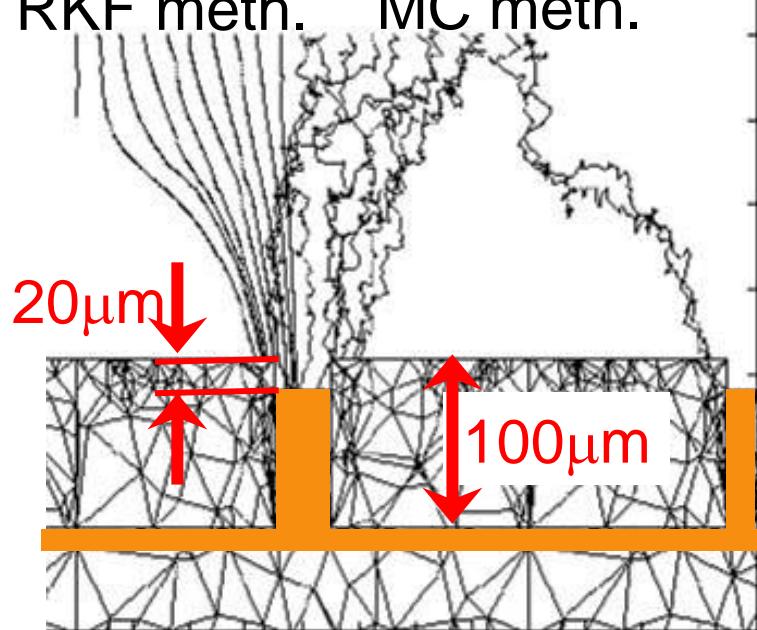


Position resolution  
 $\sigma \sim 160 \mu\text{m}$   
(knife edge test)

## 2.1 Drift simulation ~ For the best electrode ~

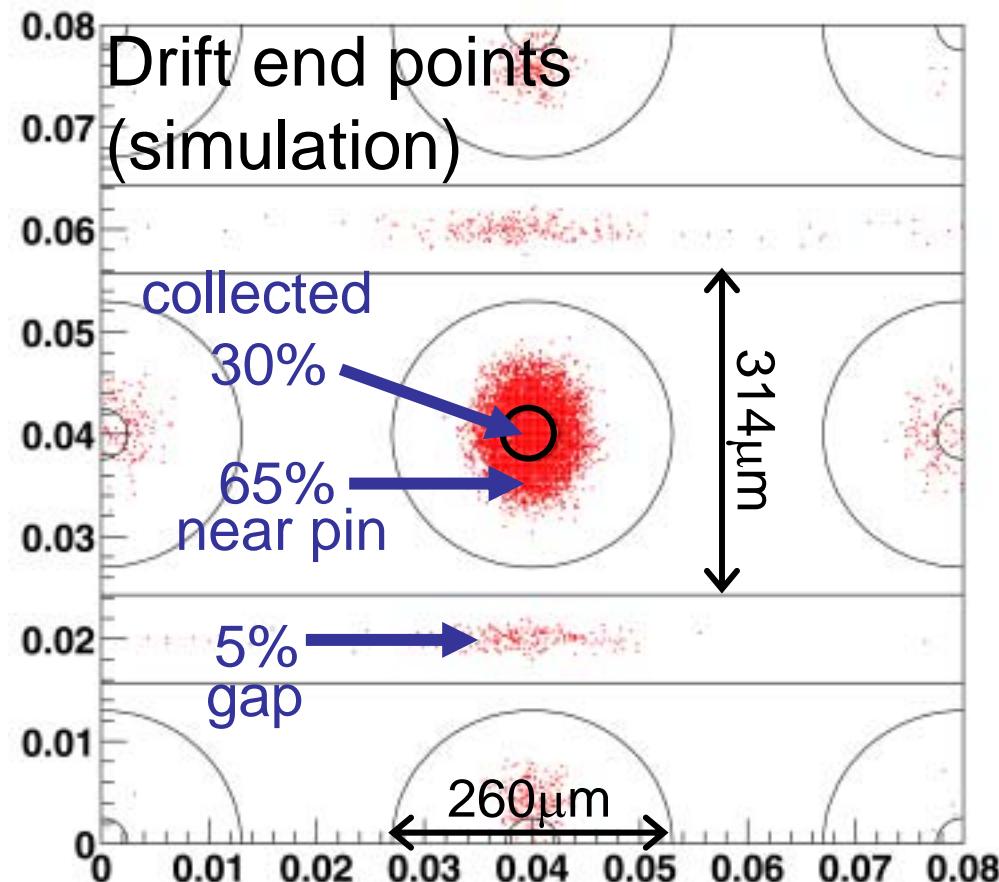
3D simulation  
(Maxwell + Garfield)

RKF meth. MC meth.



Drift paths of electrons

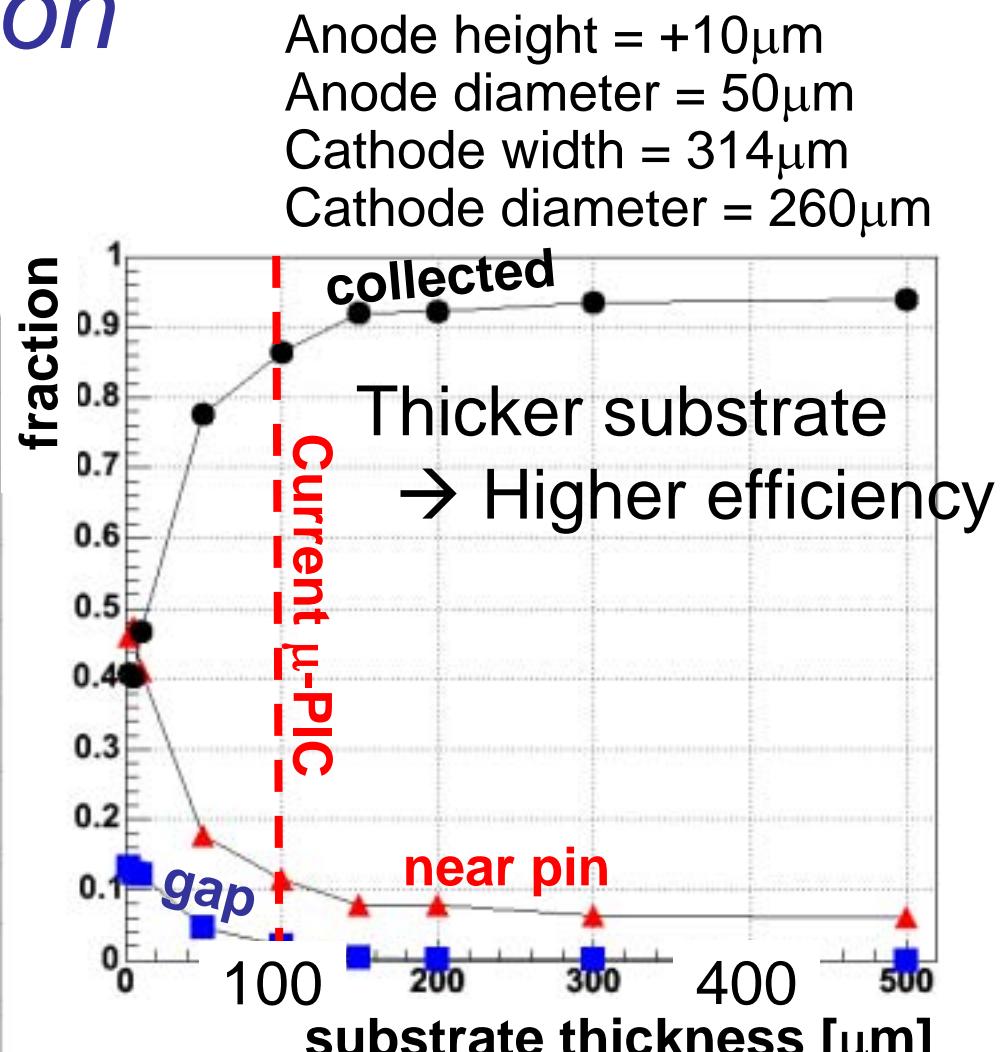
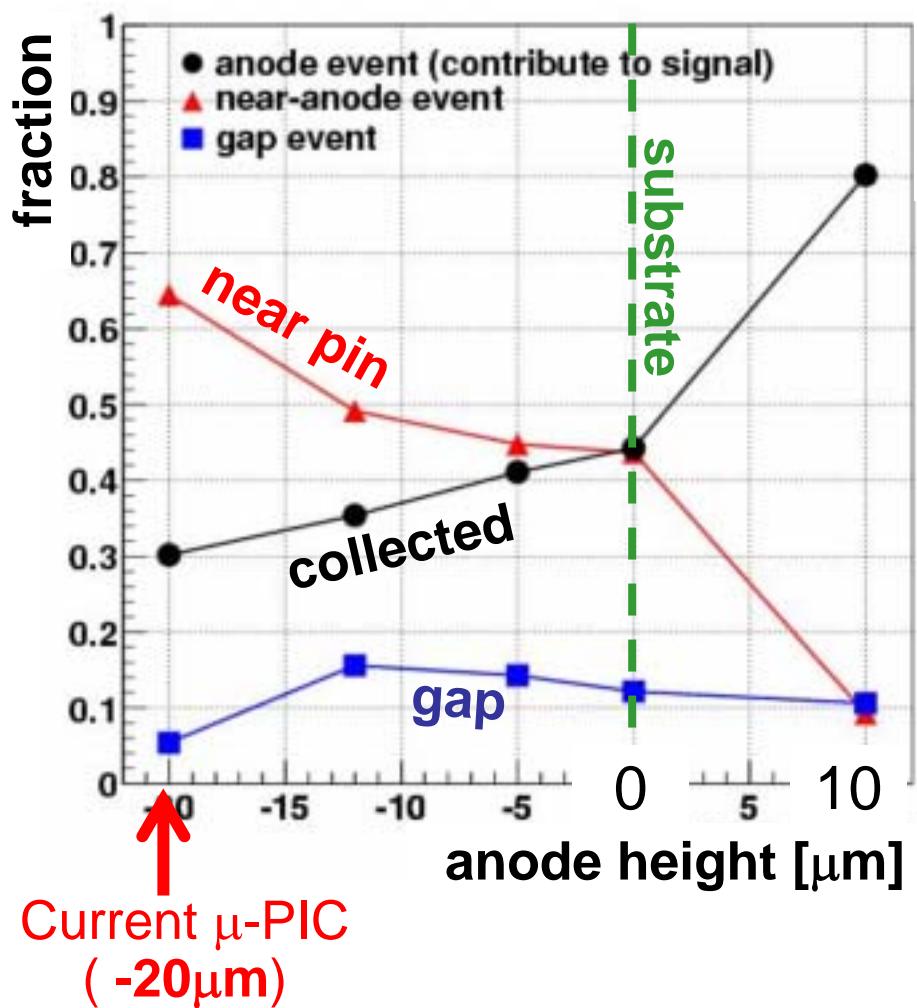
Top of anode electrodes  
are **below** substrate.



→ Collection efficiency ~ 30%

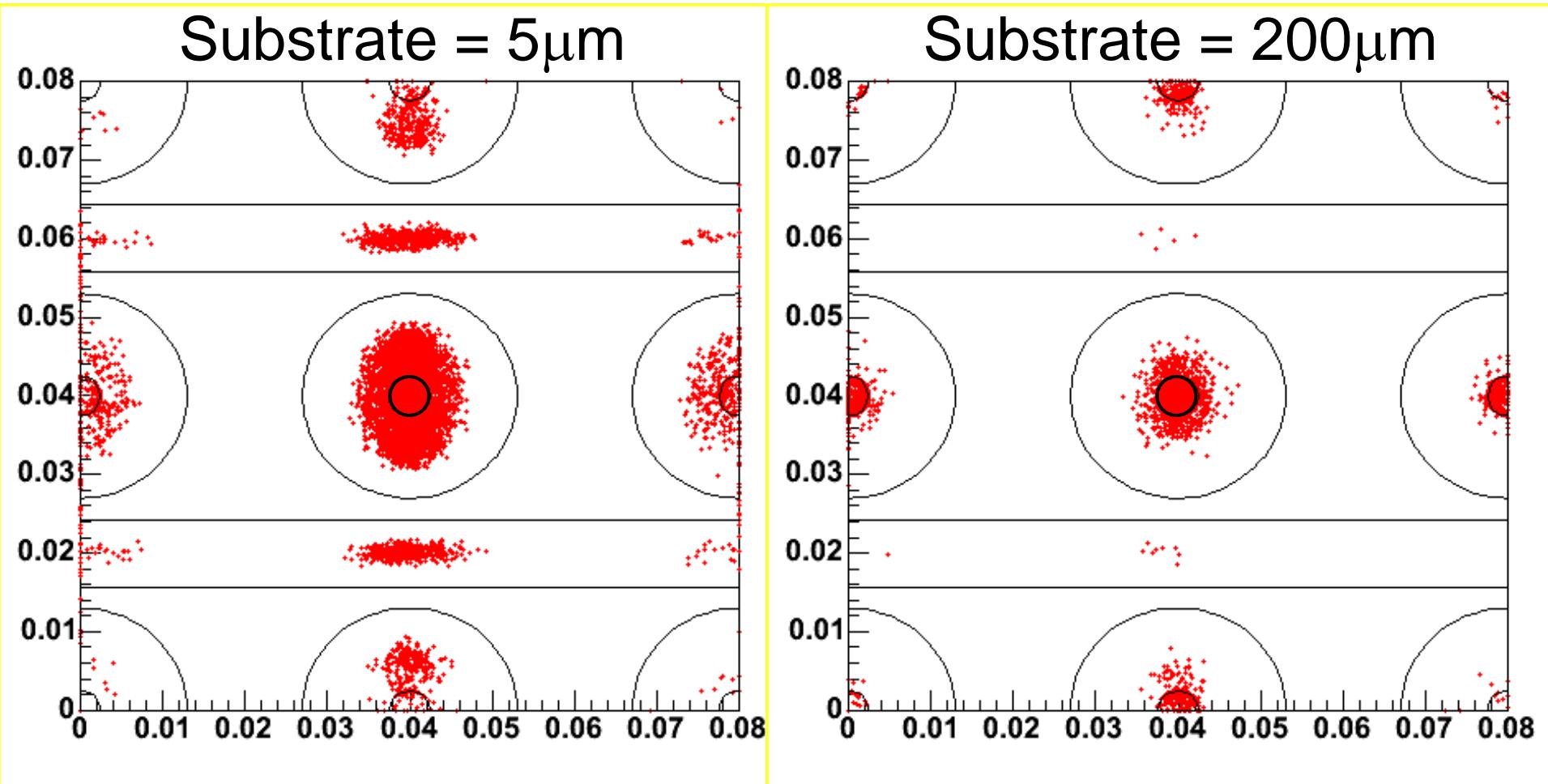
## 2.2 Drift simulation

Higher anode  
→ Higher efficiency



Substrate > 200μm ... difficult  
Anode = 10μm ... possible!!

# *Drift end points*



## 2.3.1 New $\mu$ -PIC

Electrode formation process

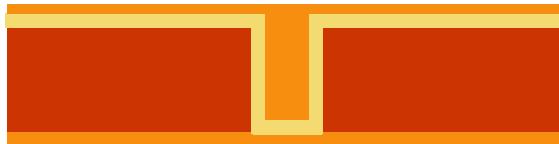
- Current type
  - ... normal plating ("bottom-up")

- New type
  - ... plating and etching ("top-down")

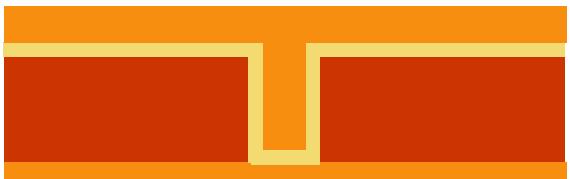
1. Electroless plating



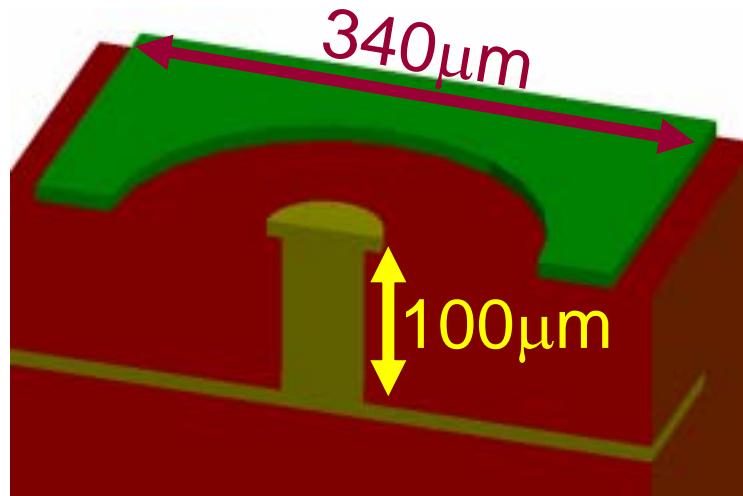
3. Surface etching



2. Via-fill plating



4. Electrode etching

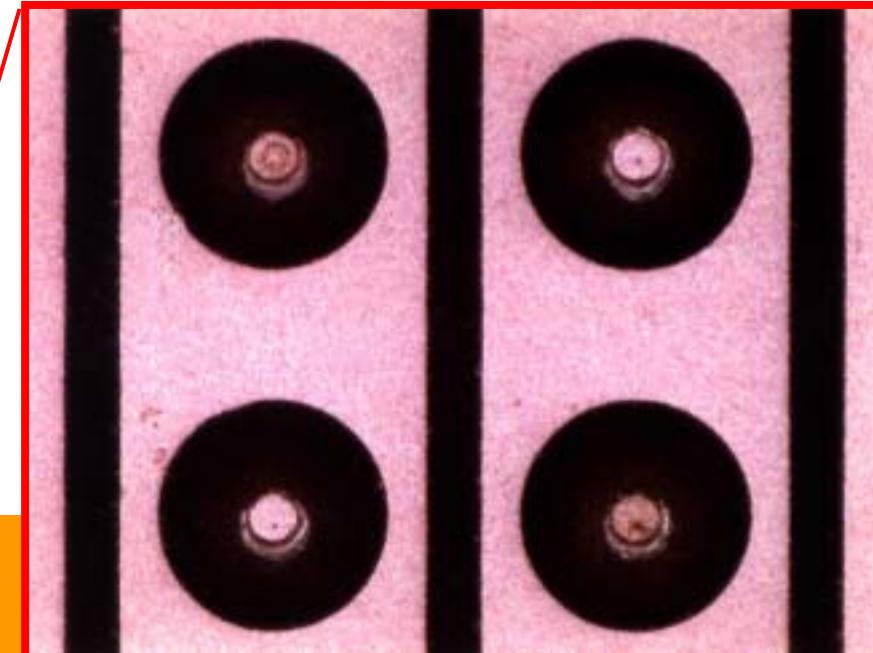
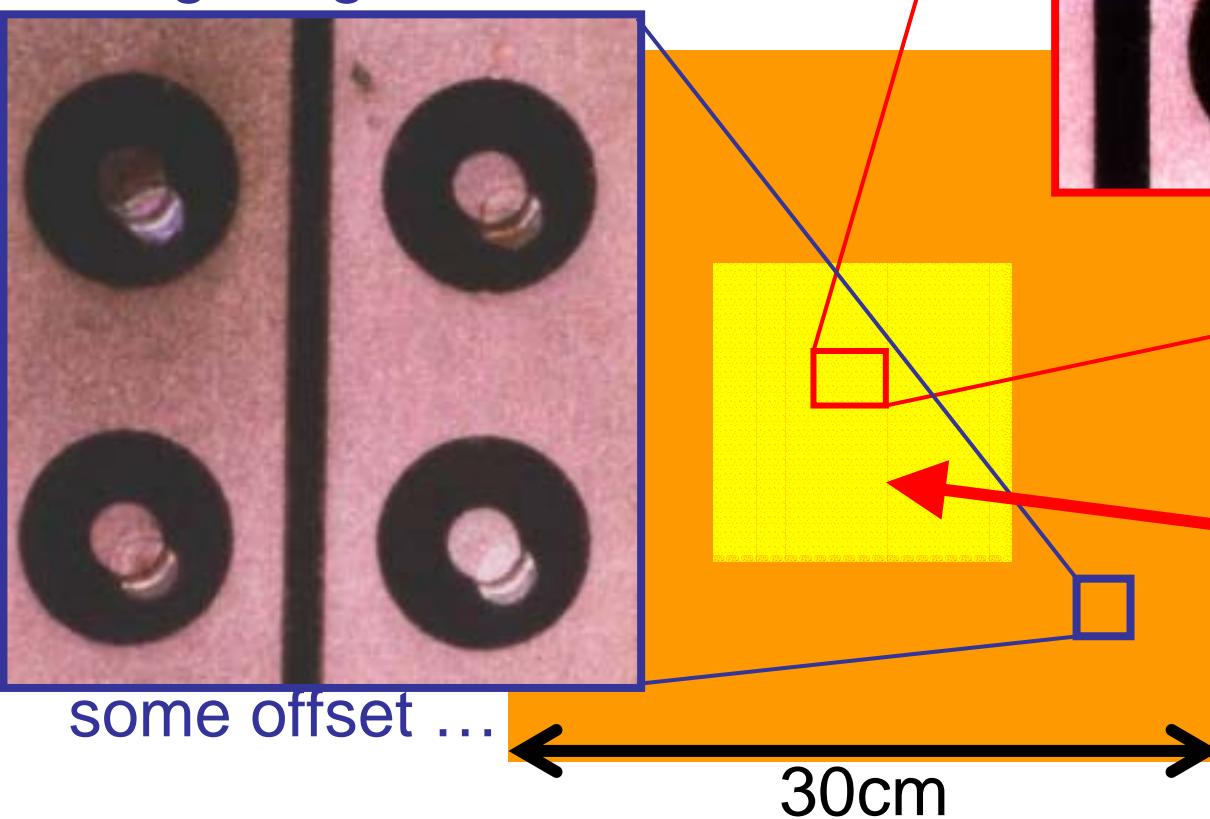


*Coming soon!!*  
Detection area  
30cm × 30cm

## 2.3.2 New $\mu$ -PIC

$30 \times 30 \text{ cm}^2$  detector

Edge region



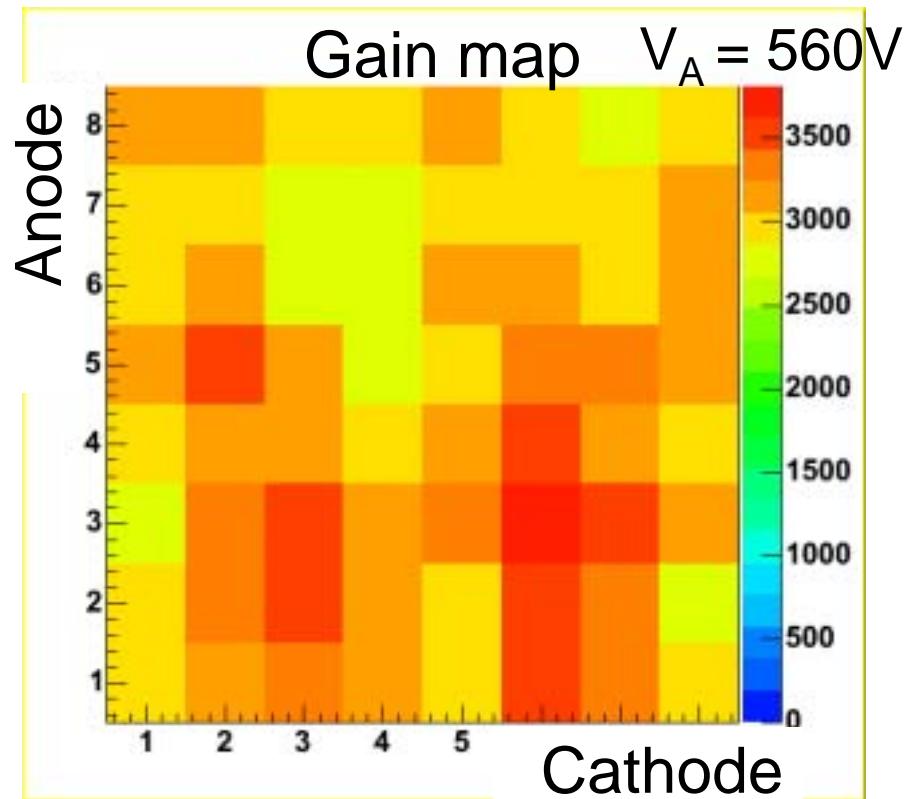
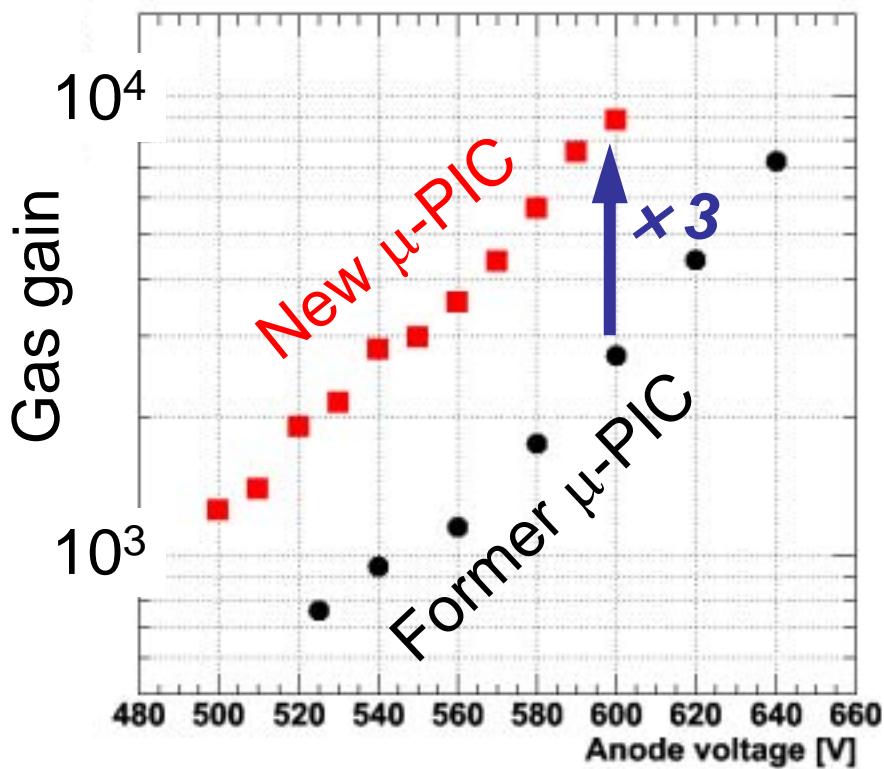
~~Center region~~

~~Beautiful!~~

$10 \times 10 \text{ cm}^2$  :  
Available for  
performance test

## 2.3.3 New $\mu$ -PIC

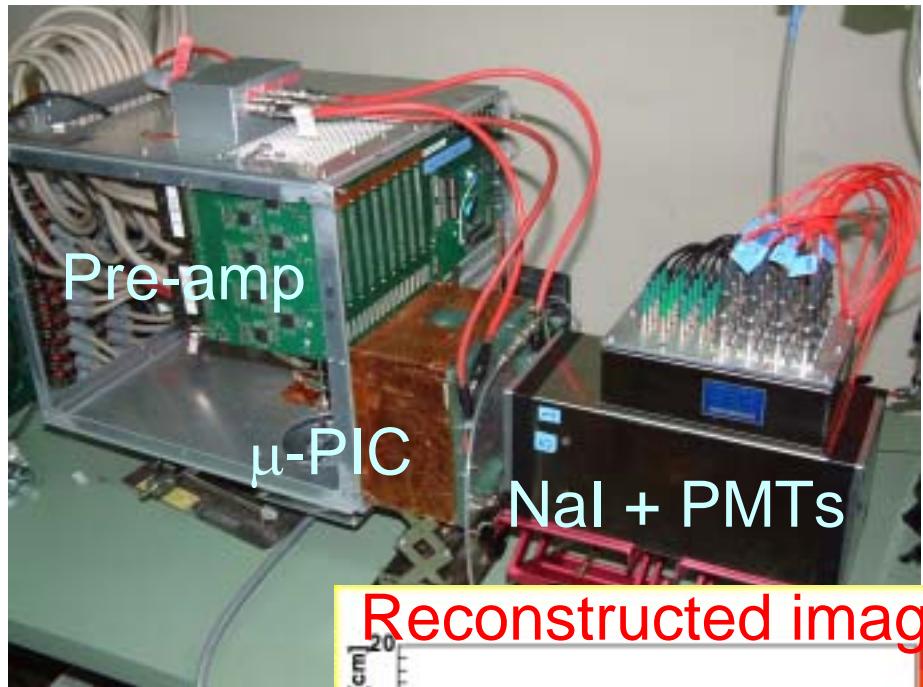
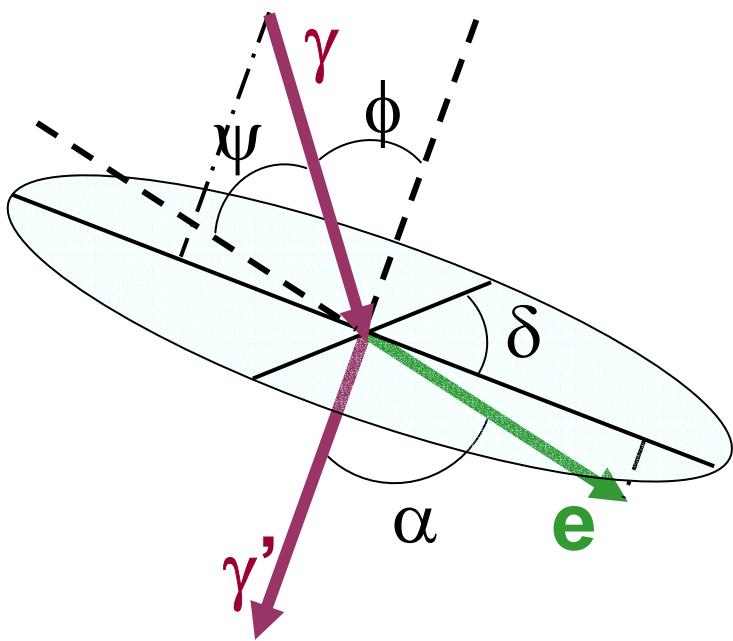
- $10 \times 10\text{cm}^2$  detection area
- Bad electrode < 0.1%
- Leakage current  
 $< 2\text{nA} @ 800\text{V}$  (in air)



- uniform anodes
- anode height  
= cathode thickness
- gas gain  $\sim 9000 @ V_A = 600\text{V}$
- gain uniformity ( $\sigma$ )  
 $\sim 7\%$



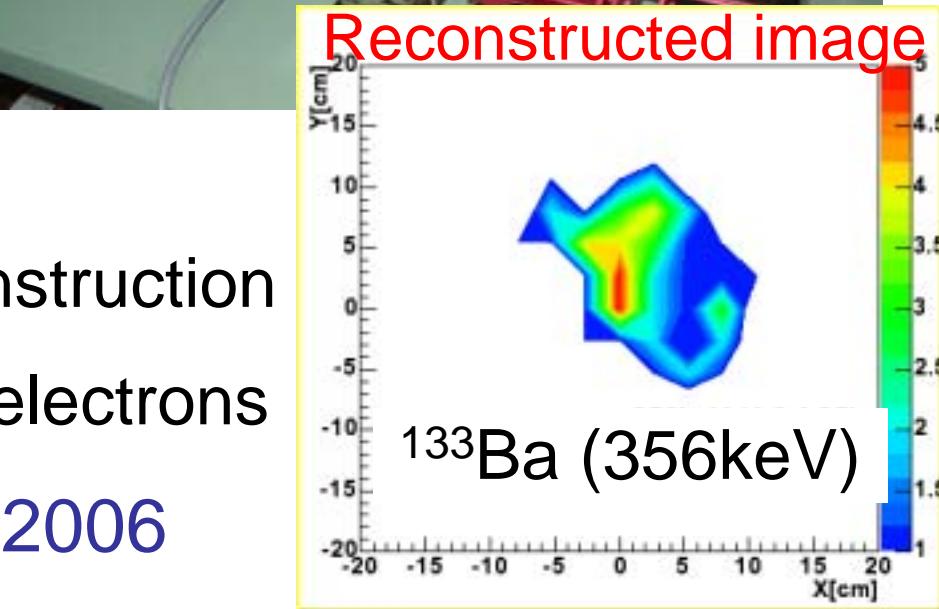
### 3.1 Gamma-ray imaging



Compton scattering

- Electron tracking → Full reconstruction
- Cross section  $\sigma \propto$  number of electrons

Balloon experiment in 2006



### 3.2.1 Gas study ~ Ar vs. $CF_4$ ~

Ar

- Number of electrons = 18
- W value = 26 eV/pair
- $(dE/dx)_{min} = 2.44 \text{ keV/cm}$

*Standard gas  
for gas detectors*

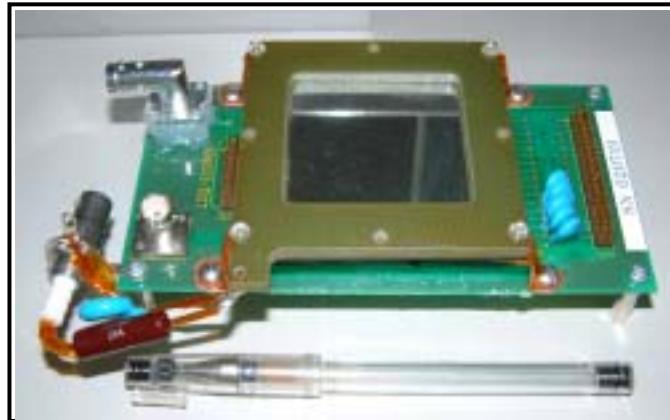
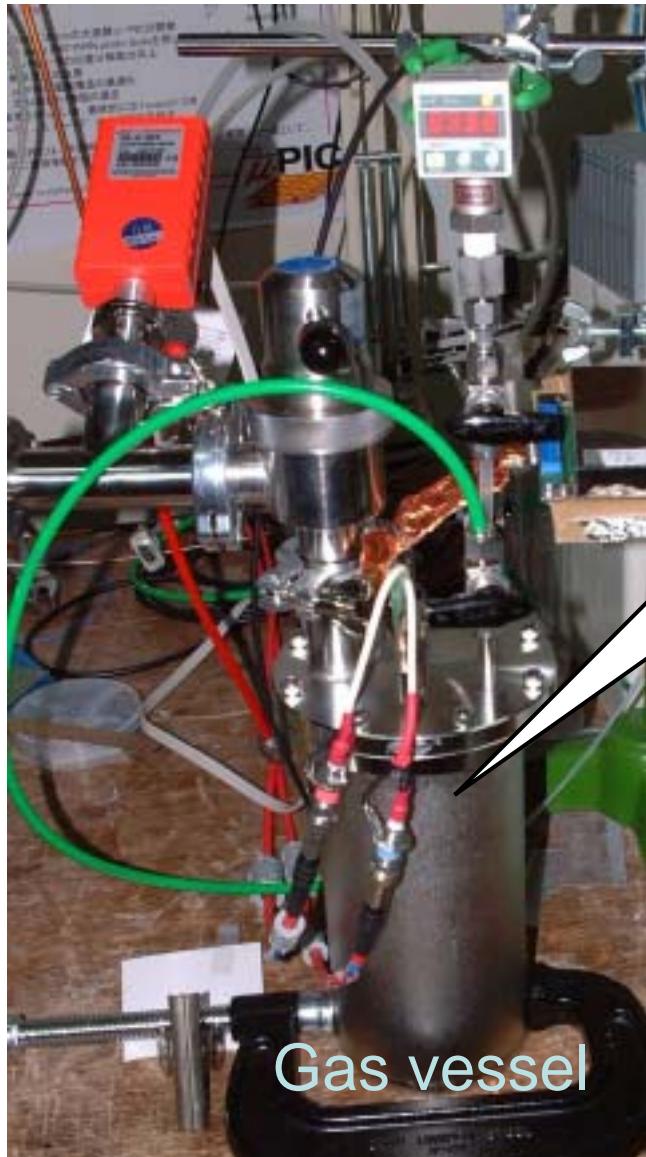
$CF_4$

- Number of electrons = 42
- W value = 54 eV/pair
- $(dE/dx)_{min} = 7 \text{ keV/cm}$
- Fast drift (~9cm/ $\mu\text{s}$ ), small diffusion

*Good properties  
for MIPs!*



### 3.2.2 Operation test



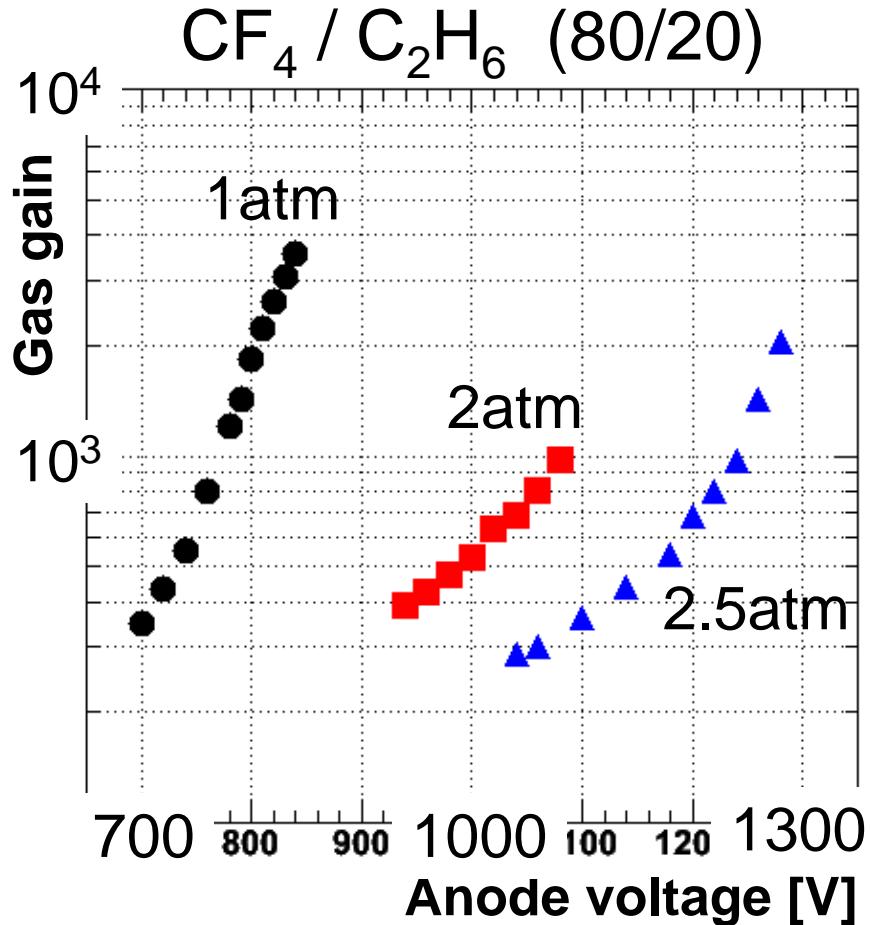
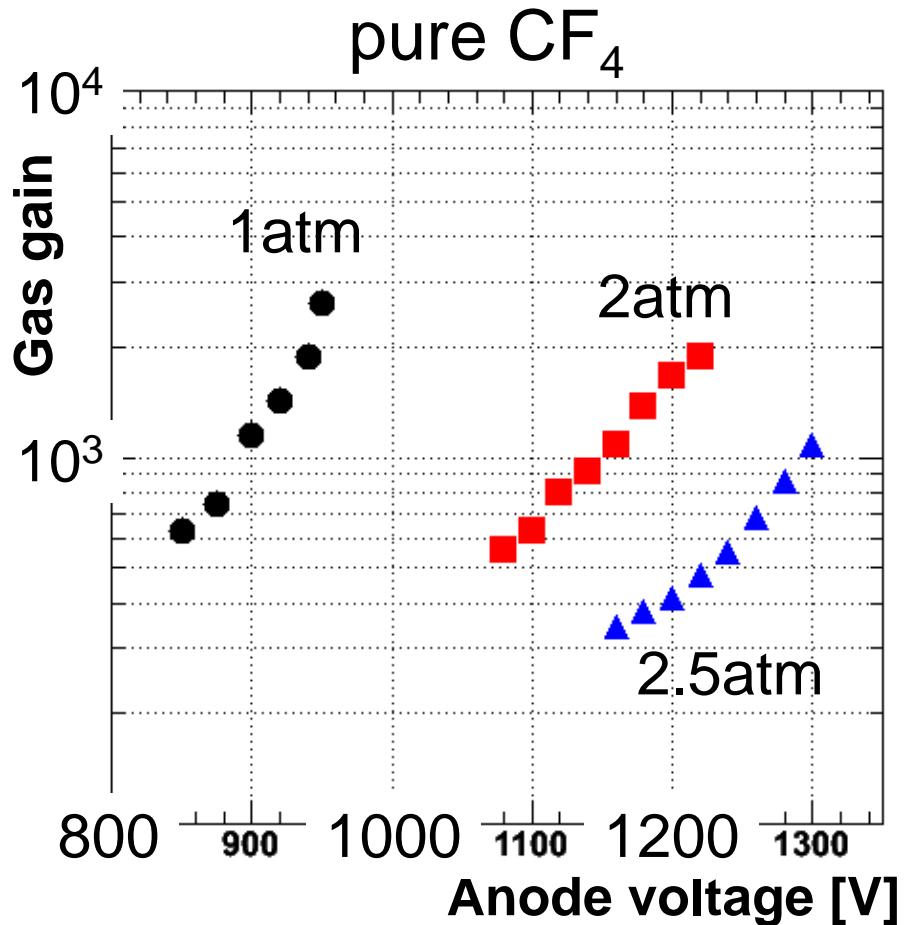
Operation test with  $\text{CF}_4$  gas

Dependence on ...

- Mixture ratio ( $\text{C}_2\text{H}_6$ )
- Pressure (1 – 2.5atm)

Source:  $^{55}\text{Fe}$  (5.9keV)

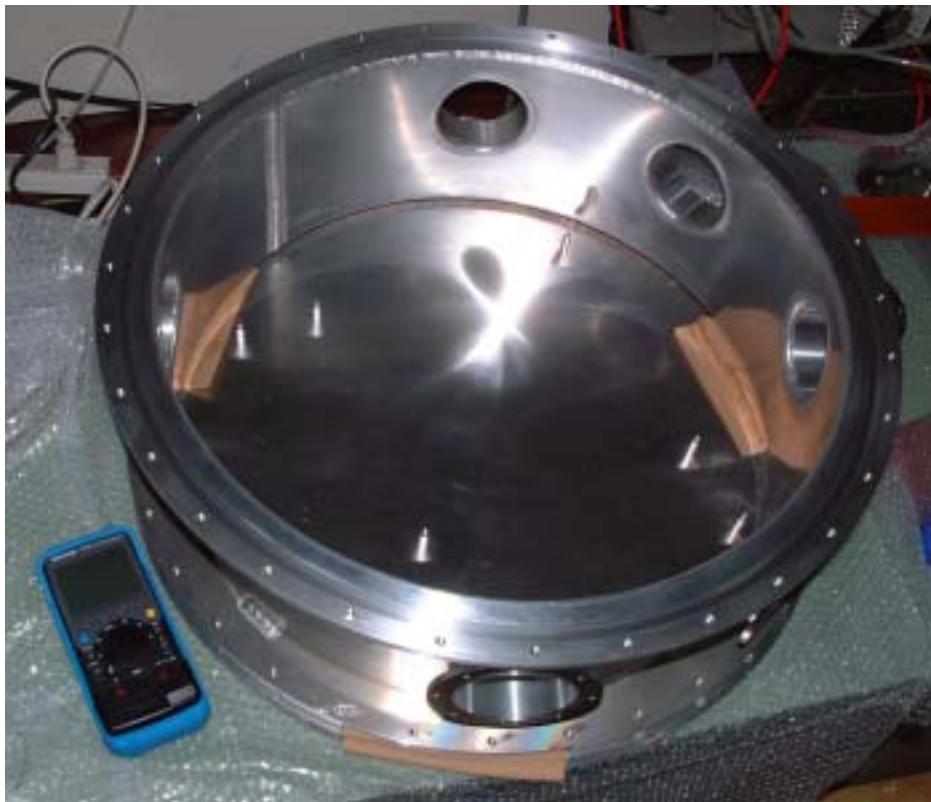
### 3.2.3 Operation test



- Maximum gas gain  $\sim 3500$  (80/20 mixture)
- Gas gain  $> 10^3$  @ 2.5atm

### 3.3 Gas vessel

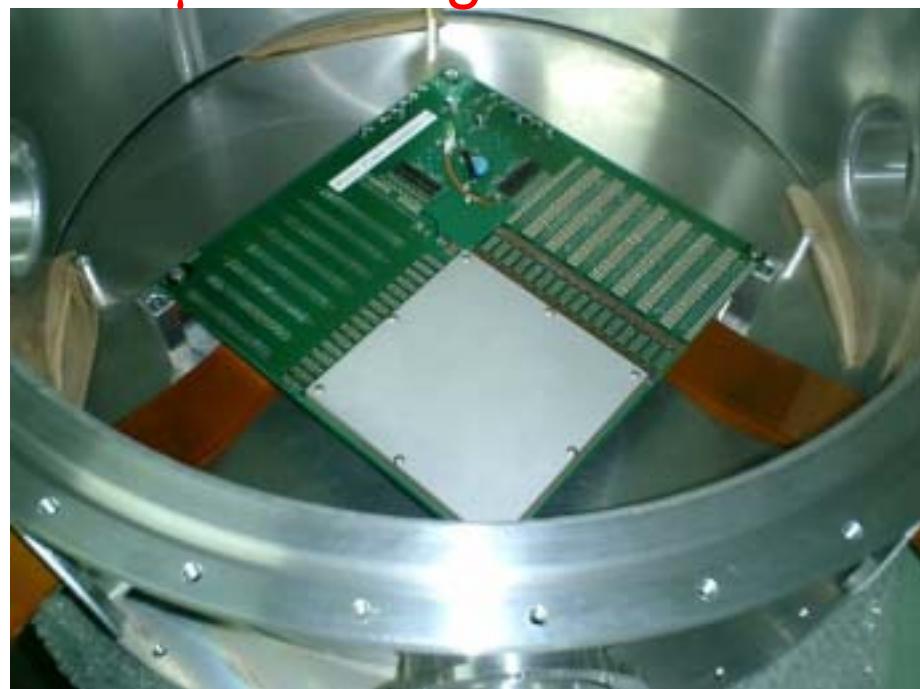
- Available for  
 $30 \times 30 \text{ cm}^2$  detector
- Vacuum ~ 4atm (?)



Flexible boards for read-out



$\mu$ -PIC in gas vessel



## 4 Summary

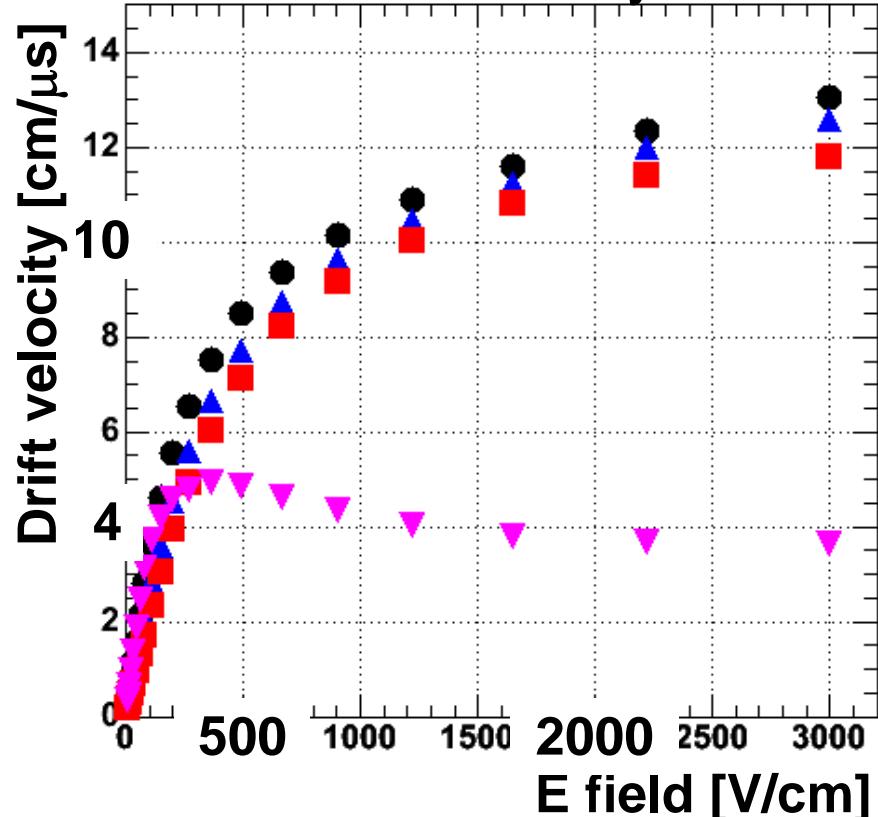
- 3D simulation of  $\mu$ -PIC
  - Higher anode → high efficiency ( > 90%)
- A new manufacture technology
  - Anode height = cathode thickness
  - Gas gain ~ 9000
  - Uniformity:  $\sigma \sim 7\%$
- $\text{CF}_4$  gas
  - Stable operation @ gas gain > 1000
- Gas vessel for  $30 \times 30\text{cm}^2$  detector
  - Pressure-resistant test is in progress



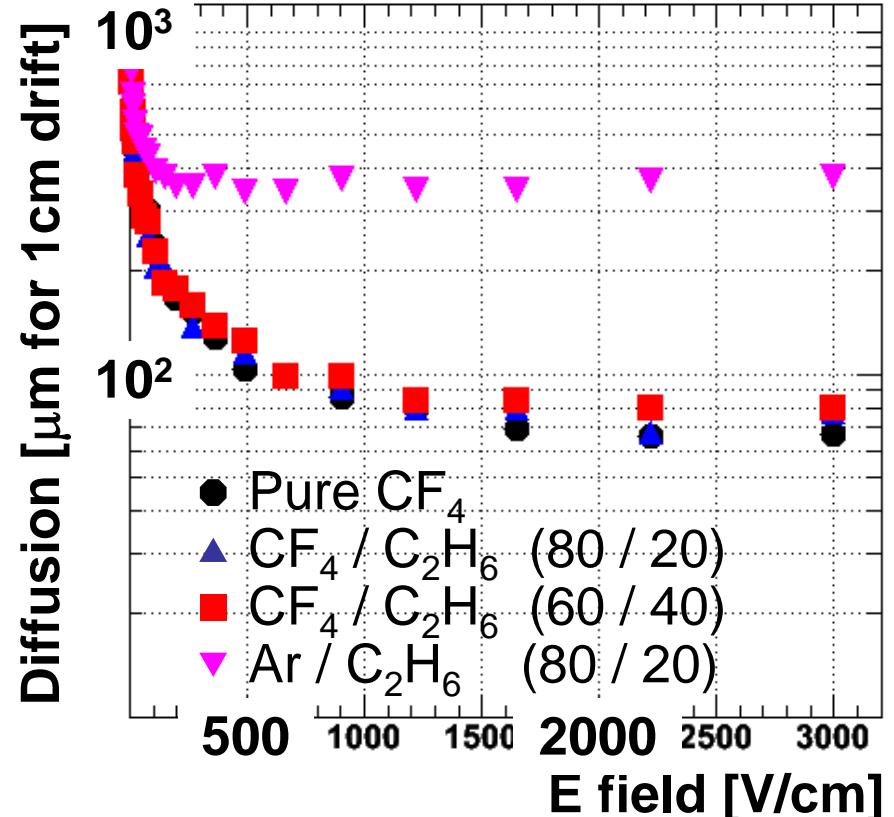
### 3.2.1 Drift and diffusion

~ Simulation by Magboltz ~

Drift velocity



Diffusion



- Drift:  $\times 2$  faster than Ar
- Diffusion:  $1/4$  smaller than Ar